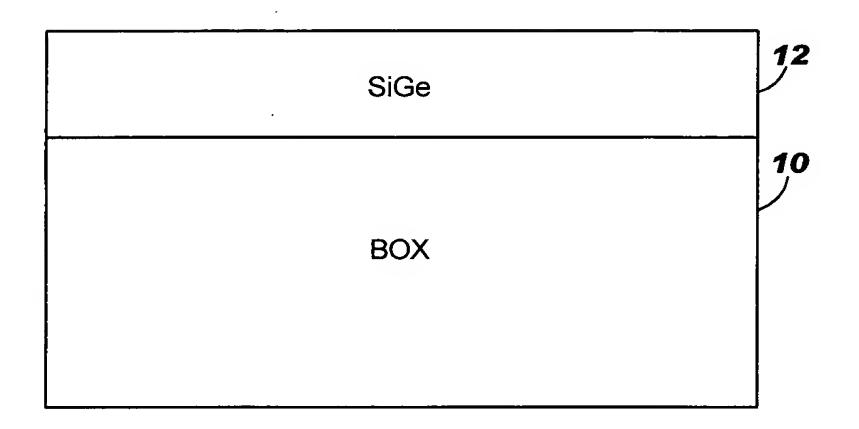
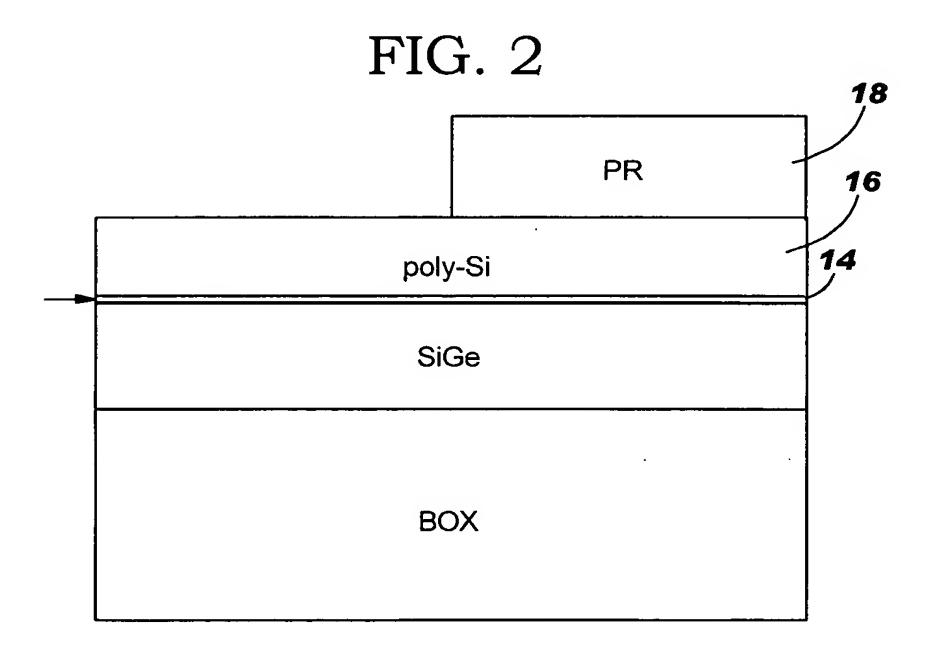
FIS920030239US1 (TLT) Steven W. Bedell, et al.

1/10

FIG. 1





2/10

FIG. 3

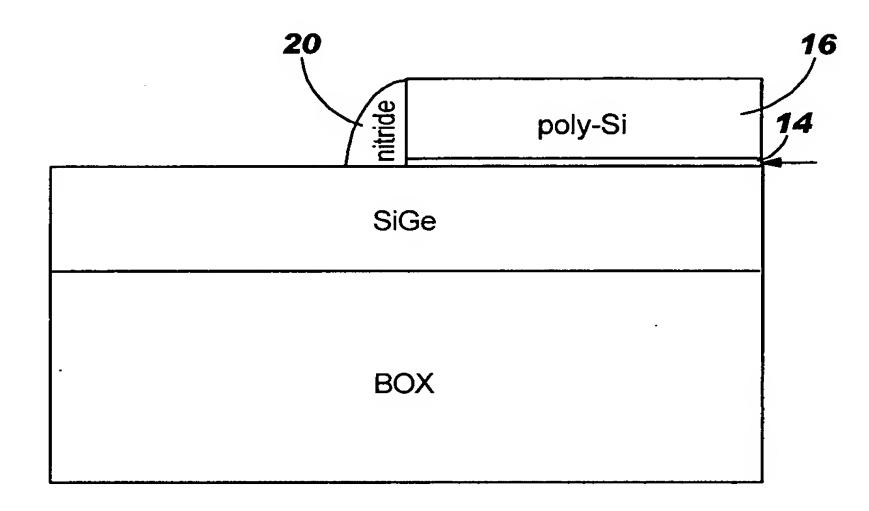
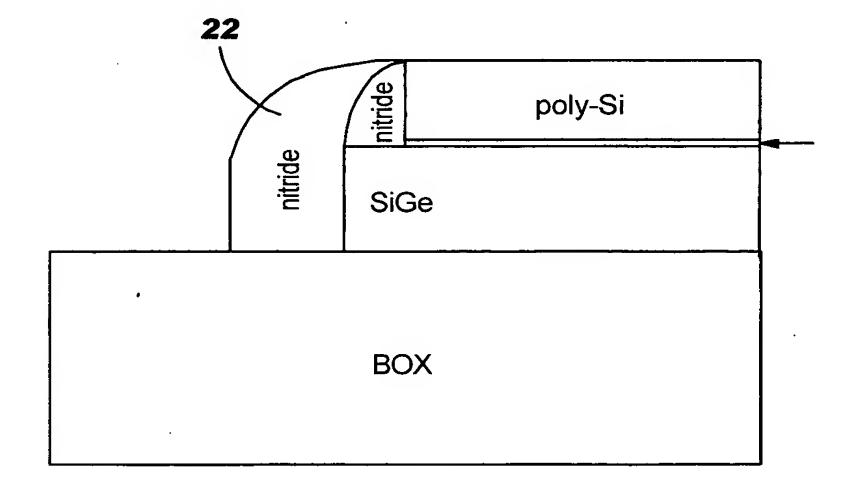


FIG. 4



3/10

FIG. 5

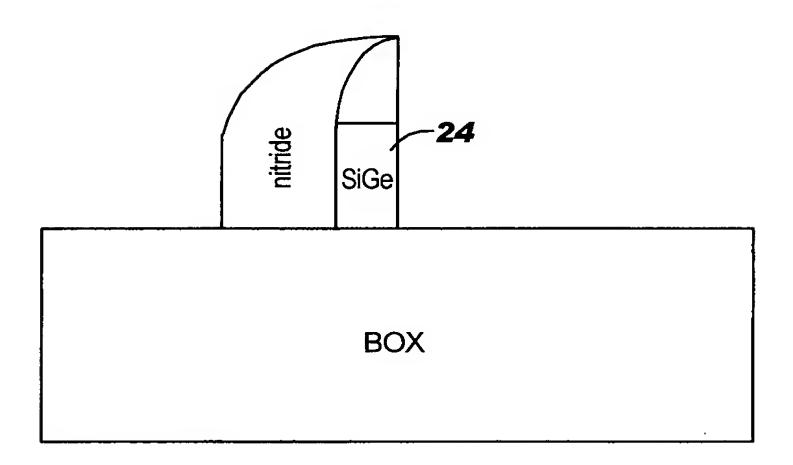
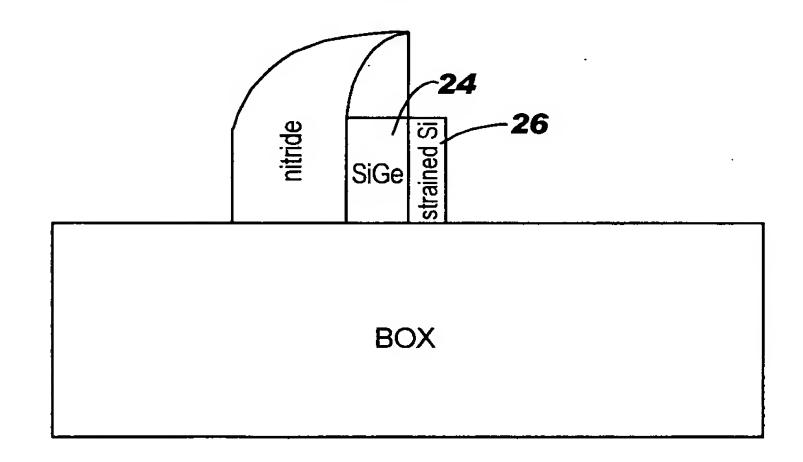


FIG. 6



4/10

FIG. 7

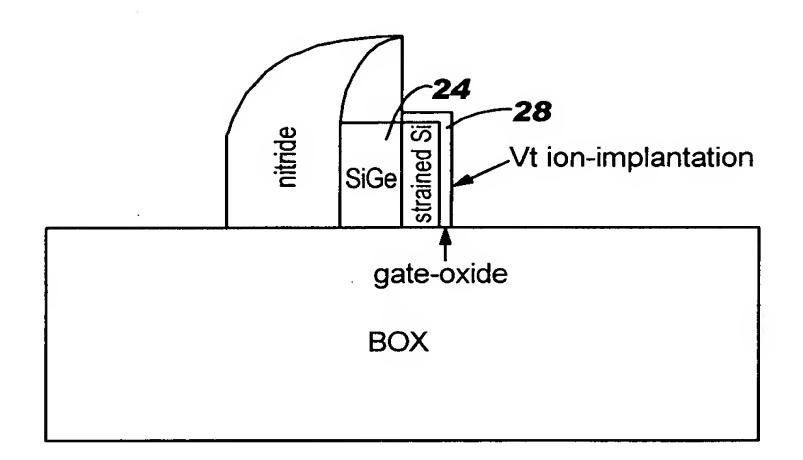
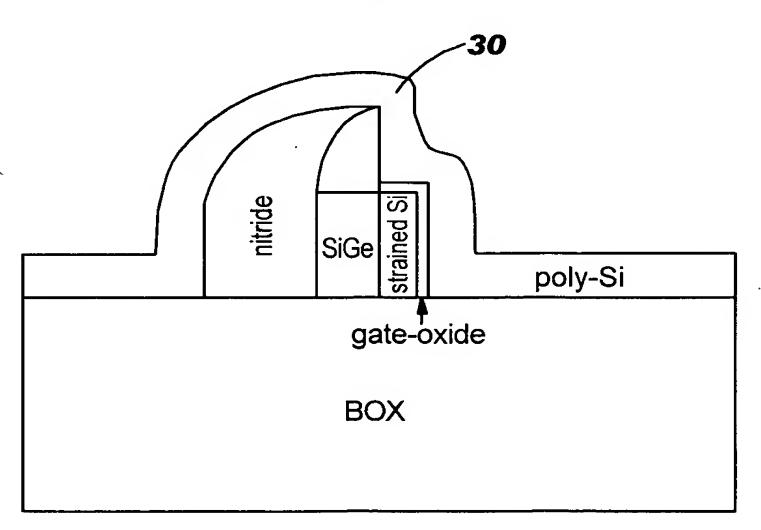


FIG. 8



5/10

FIG. 9

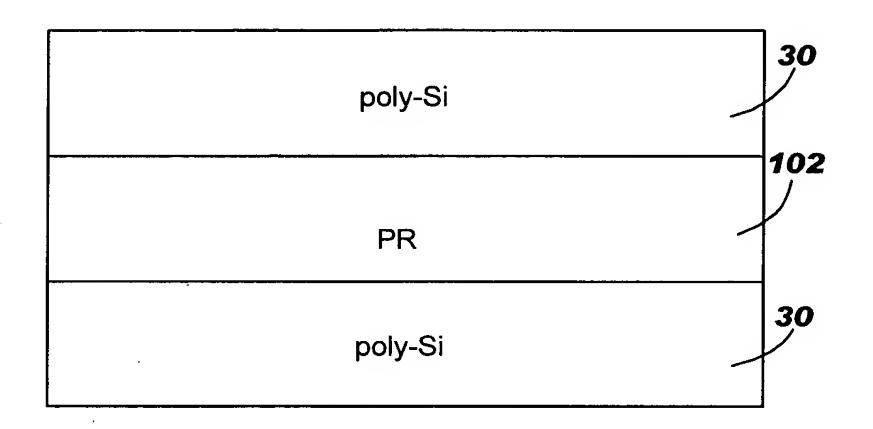


FIG. 10

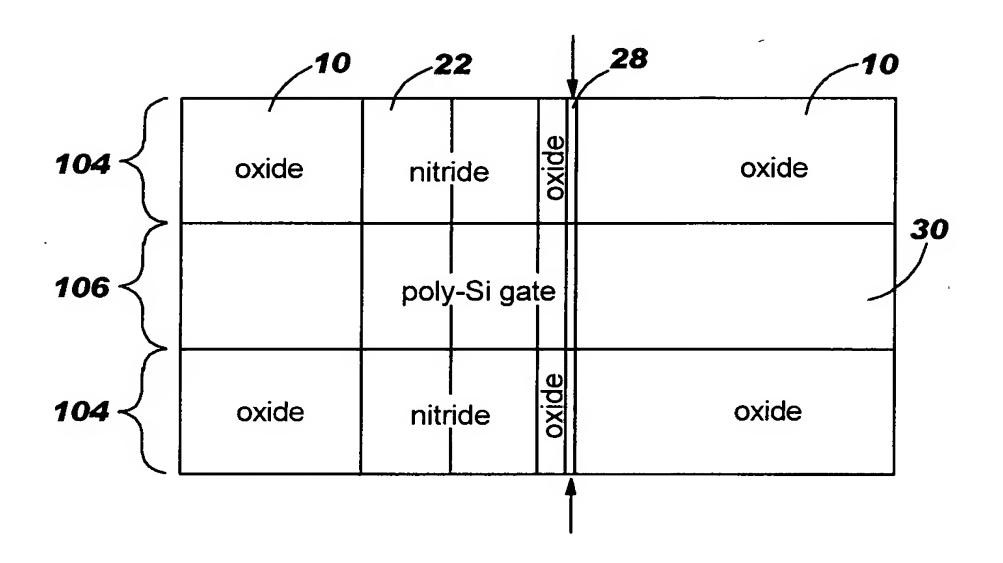
PR

102

SiGe introduction poly-Si gate-oxide

6/10

FIG. 11



7/10

FIG. 12

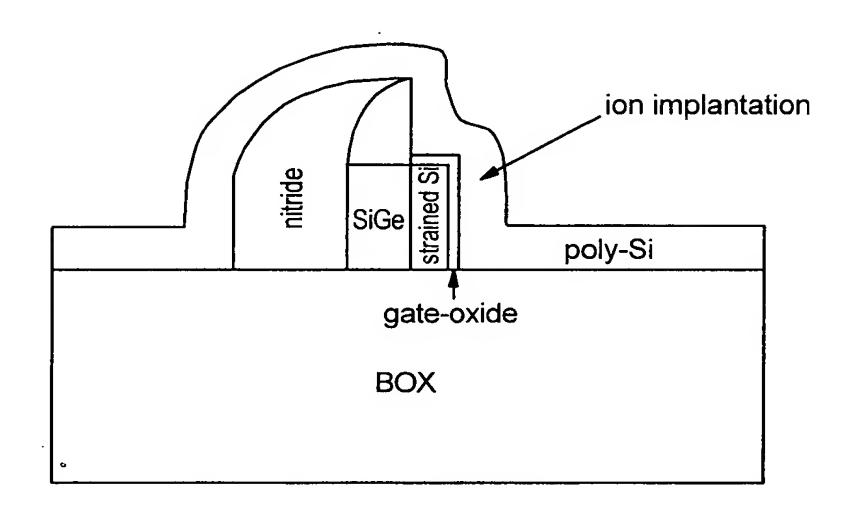
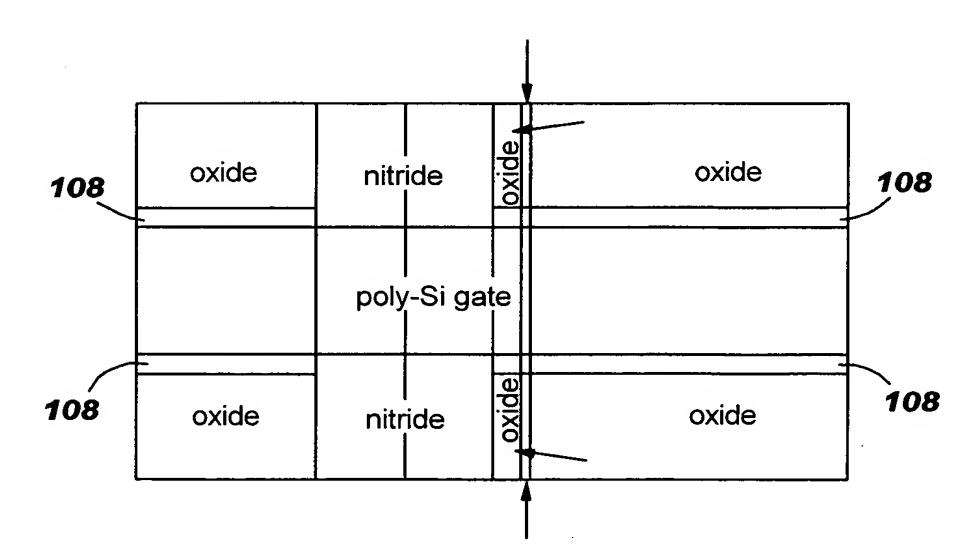


FIG. 13



8/10

FIG. 14

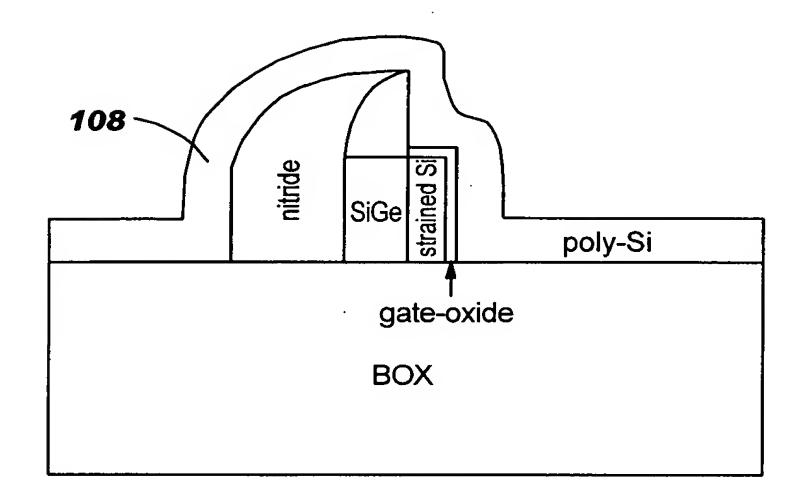
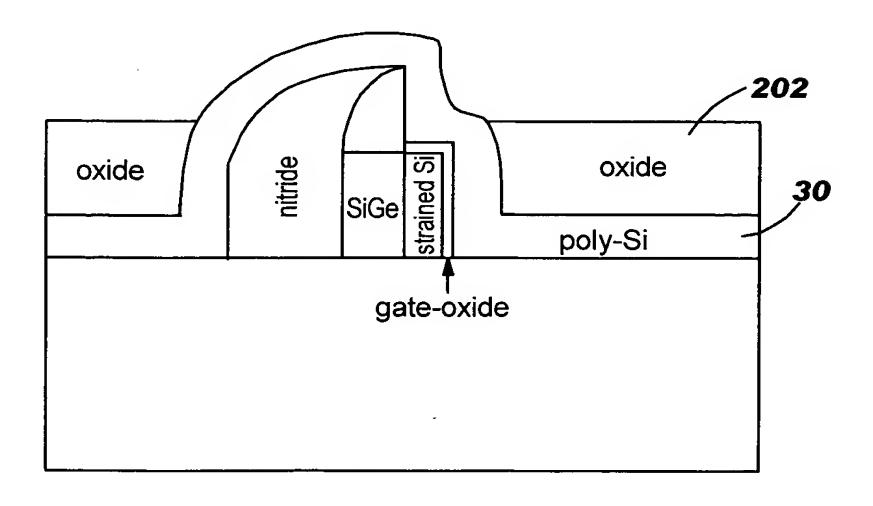


FIG. 15



9/10

FIG. 16

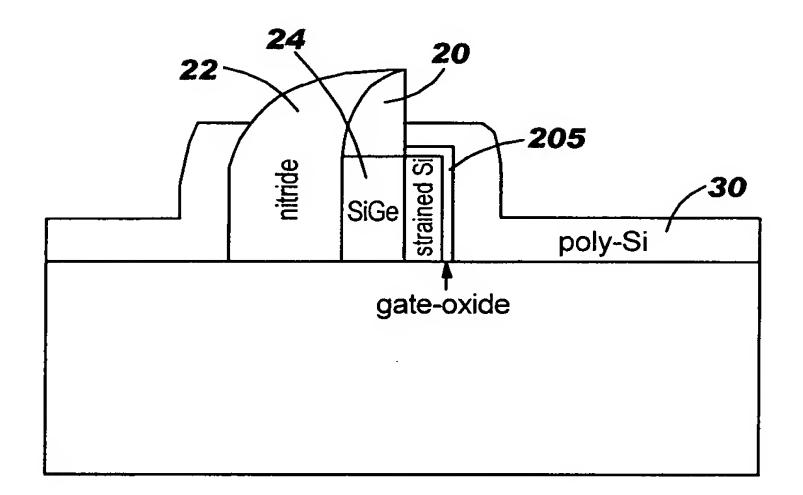
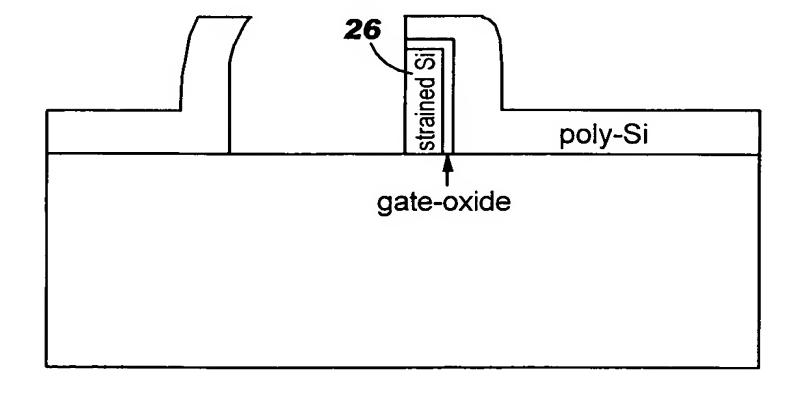


FIG. 17



10/10

FIG. 18

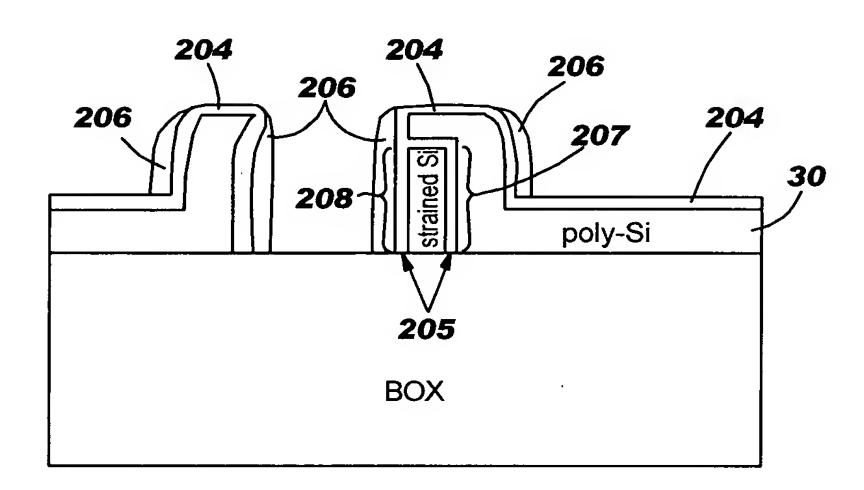


FIG. 19

